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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/797,618	03/11/2004	Sven Antoin Johan Hol	081468-0308420	6457
909	7590	06/30/2005	EXAMINER	
PILLSBURY WINTHROP SHAW PITTMAN, LLP				KIM, PETER B
P.O. BOX 10500				
MCLEAN, VA 22102				
				ART UNIT
				PAPER NUMBER
				2851

DATE MAILED: 06/30/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

EJC

Office Action Summary	Application No.	Applicant(s)	
	10/797,618	JOHAN HOL ET AL.	
Examiner	Art Unit	Peter B. Kim	2851

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on ____.
- 2a) This action is **FINAL**. 2b) This action is non-final.
- 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 1-21 is/are pending in the application.
- 4a) Of the above claim(s) ____ is/are withdrawn from consideration.
- 5) Claim(s) ____ is/are allowed.
- 6) Claim(s) 1-21 is/are rejected.
- 7) Claim(s) ____ is/are objected to.
- 8) Claim(s) ____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
- 10) The drawing(s) filed on ____ is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 - a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. ____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) Notice of References Cited (PTO-892)
- 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
 Paper No(s)/Mail Date 32004.
- 4) Interview Summary (PTO-413)
 Paper No(s)/Mail Date. ____.
- 5) Notice of Informal Patent Application (PTO-152)
- 6) Other: ____.

DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 1-4, 6-15, and 17-21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kamata et al. (Kamata) (6,084,319) in view of Dombrovski (2003/0030339).

Kamata discloses a device manufacturing method and a lithographic apparatus comprising a radiation system (127), a support structure to support a patterning device (128), a substrate holder (121), a projection system (129) that projects the pattern beam onto substrate, an actuator (125) configured to position the substrate holder with a coil arrangement (42a), magnet (41a) and cooling element (42b). However, Kamata does not disclose having slits in the cooling element which reduces eddy current. Ohashi discloses an actuating mechanism with slits in the surface to increase resistance of eddy current paths (abstract). Ohashi also discloses that the slits are parallel to each other (Fig. 1, 2, 3), and slits arranged parallel or perpendicular to the induced electric field. Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to provide the slits of Ohashi to the invention of Kamata in order to increase electric resistance to eddy current as taught by Ohashi in the abstract.

Claims 1, 5, 11, 12 and 16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kamata et al. (Kamata) in view of Inoue et al. (Inoue) (2003/0048167).

Kamata discloses a device manufacturing method and a lithographic apparatus comprising a radiation system (127), a support structure to support a patterning device (128), a substrate holder (121), a projection system (129) that projects the pattern beam onto substrate, an actuator (125) configured to position the substrate holder with a coil arrangement (42a), magnet (41a) and cooling element (42b). However, Kamata does not disclose having slits at an oblique angle to the induced electric field in the cooling element which reduces eddy current. Inoue discloses an actuator comprising a magnet, a coil and slits (Fig. 5A, 6A, 7A) at an oblique angle to the electric field to reduce eddy current (para 0067). Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to provide the slits of Inoue to the invention of Kamata in order to reduce eddy current as taught by Inoue in para 0067.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Peter B. Kim whose telephone number is (571) 272-2120. The examiner can normally be reached on 8:00 AM - 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on (571) 272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2851

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Peter B. Kim
Primary Examiner
Art Unit 2851

June 23, 2005